

Accelerate Your Research

Flexible Nitride MOCVD with Simplified Operation

SR4000HT-RR

- Based on Proven and Reliable SR Series Design
- Tailored for Research Environments, Incorporating Established SR4000HT Capabilities in a Smaller Package

Wide Process Window MOCVD for Power and Optoelectronic Devices

Advantages

- High Growth Rates
- Carbon Background Concentration Control and Flexibility
- High InGaN Growth Temperature
- High Al Content AlGaN

Applications

HEMT, PN Diodes, Lasers, RGB to UV LED





SR4000HT-RR Specifications

Reactor type	Face up, horizontal with rotation
Wafer size	2" x 3 or 4" x 1
Heating system	Two zone, up to 1350 °C
Growth pressure	10 kPa up to 100 kPa
Size	One cabinet only for manifold, reactor and exhaust
Sources	Eight (8) metalorganic Two (2) hydride lines

About Us

Taiyo Nippon Sanso is an industrial gas manufacturer established in 1910. As an innovator in the compound semiconductor industry, Taiyo Nippon Sanso was the first company to introduce commercial MOCVD systems, in 1983. Taiyo Nippon Sanso is uniquely qualified to provide total solutions for compound semiconductor fabrication, with MOCVD equipment, gas handling and purification equipment, exhaust abatement solutions, and custom piping and installation services. Taiyo Nippon Sanso has delivered a large quantity of MOCVD equipment worldwide for numerous applications, ranging from R&D to mass production. Our technology is highly regarded worldwide for its exceptionally stable performance.



Visit our website www.MOCVD.jp

TAIYO NIPPON SANSO Corporation

Address: Toyo Bldg., 1-3-26 Koyama, Shinagawa-ku, Tokyo 142-8558, Japan E-mail: U05782@tn-sanso.co.jp TEL: (81) 03-3457-9220

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